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Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1-10. (Canceled)

11. (Currently Amended) A manufacturing method for exposure apparatuses which expose a second object by an exposure beam via a first object and a projection system, comprising:

a first step of assembling a first main body frame of an exposure apparatus in a first manufacturing line;

a second step of assembling a second main body frame of an exposure apparatus in a second manufacturing line;

a third step of installing a first adjustment stage in the first main body frame at a position where a stage which ~~aligns~~ moves the first object ~~of the first main body frame~~ is placed in the first manufacturing line, and assembling and adjusting an illumination system to be mounted on the first main body frame;

a fourth step of assembling and adjusting a stage system which aligns the first object and the second object using the second main body frame in the second manufacturing line; and

a fifth step of removing the first adjustment stage from the first main body frame in the first manufacturing line, mounting the projection system and the stage system removed from the second main body frame on the first main body frame to assemble ~~the~~ a first exposure apparatus.

12. (Currently Amended) The manufacturing method for exposure apparatuses according to Claim 11, wherein ~~the~~ a second exposure apparatus is assembled and adjusted using the second main body frame in the second manufacturing line after the fifth step.

13. (Currently Amended) The manufacturing method for exposure apparatuses, according to claim 11, wherein the fifth step further comprises:

a first sub-step for mounting the projection system on the first main body frame;

a second sub-step for mounting ~~the~~ a second adjustment stage on the first main body frame at a position where ~~the~~ a stage which ~~aligns~~ moves the second object is placed, in order to adjust the projection system;

a third sub-step for removing the first and second adjustment stages from the first main body frame; and

a fourth sub-step for mounting the stage system removed from the second main body frame on the first main body frame.

14. (Currently Amended) The manufacturing method for exposure apparatuses according to Claim 11, wherein the first adjustment stage further comprises a pin hole which is movable two-dimensionally and a photo-electric detector which detects the exposure beam which passes through the pin hole, and optical information with respect to ~~by an optical Fourier transform surface, and dispersion of coherence~~ factors of the illumination system is measured by the first adjustment stage.

15. (Currently Amended) The manufacturing method for exposure apparatuses according to Claim 11, wherein the first exposure apparatus is a scanning type exposure apparatus which moves the first object and the second object in a predetermined scanning direction synchronously to execute exposure, the first adjustment stage comprises a pin hole which is movable in a non-scanning direction which crosses the scanning direction, and a photo-electric detector which detects the exposure beam which passes through this pin hole, and substantially two-dimensional illuminance unevenness of the ~~illumination system~~ exposure beam is measured using the first adjustment stage.

16. (Currently Amended) The manufacturing method for exposure apparatuses according to Claim 13, further comprising a step of assembling and adjusting ~~the an~~ illumination system to be mounted on the second main body frame to assemble a second exposure apparatus by mounting the removed first adjustment stage on the second main body frame at a position where ~~the a~~ stage which ~~aligns-moves~~ the first object ~~of the second main body frame in the second exposure apparatus~~ is placed in the second manufacturing line after removing the stage system from the second main body frame in the second manufacturing line.

17. (Currently Amended) The manufacturing method for exposure apparatuses according to Claim 16, further comprising a step of mounting the removed second adjustment stage on the second main body frame at a position where ~~the a~~ stage which ~~positions-moves~~ the second object in the second exposure apparatus is placed in order to adjust ~~the a~~ projection system of the second exposure apparatus in the second manufacturing line.

18. (Currently Amended) The manufacturing method for exposure apparatuses according to Claim 11, wherein the first exposure apparatus is a scanning type exposure apparatus which moves the first object and the second object in a predetermined scanning direction synchronously to execute exposure, the first adjustment stage comprises a slit which can move in a non-scanning direction which crosses the scanning direction, and a photo-electric detector which detects the exposure beam which passes through this slit, and substantially two-dimensional illuminance unevenness of the ~~illumination system~~ exposure beam is measured using the first adjustment stage.

19. (Original) The manufacturing method for exposure apparatuses according to Claim 11, wherein the stage system installed to the second main body frame is adjusted based on a positional relationship between the first main body frame and the first adjustment stage.

20. (Original) The manufacturing method for exposure apparatuses according to Claim 13, wherein the stage system installed to the second main body frame is adjusted based on a positional relationship between the first main body frame and the second adjustment stage.

21. (Original) The manufacturing method for exposure apparatuses according to Claim 20, wherein a partial illumination system at the first object side of the illumination system is slidably installed to the first main body frame, and the partial illumination system is retracted when the first adjustment stage is attached to/removed from the first main body frame and when the stage system is installed.

22-34. (Canceled)

35. (New) A manufacturing method for exposure apparatuses which expose a second object by an exposure beam via first object, comprising:

assembling a main body frame of a first exposure apparatus which includes a plurality of modules in a first manufacturing line;

installing an adjustment module to the main body frame of the first exposure apparatus to adjust a first module of the first exposure apparatus;

adjusting a second module, which is different from the first module and which is to be installed to the main body frame of the first exposure apparatus, by using a main body frame of a second exposure apparatus which is different from the first exposure apparatus and which is assembled in a second manufacturing line; and

installing in the first manufacturing line the adjusted second module, which has been removed from the main body frame of the second exposure apparatus, to the main body frame of the first exposure apparatus in order to assemble the first exposure apparatus.

36. (New) The manufacturing method for exposure apparatuses according to claim 35, further comprising:

removing the adjustment module from the main body frame of the first exposure apparatus; and

installing the adjustment module to the main body frame of the second exposure apparatus from which the adjusted second module has been removed in order to adjust a module of the second exposure apparatus.

37. (New) The manufacturing method for exposure apparatuses according to claim 35, wherein the second exposure apparatus is assembled in the second manufacturing line, and a sequence of the second manufacturing line is time-shifted from that of the first manufacturing line.

38. (New) The manufacturing method for exposure apparatuses according to claim 35, wherein:

the second exposure apparatus including a plurality of modules is assembled in the second manufacturing line; and

the plurality of modules is adjusted in a manufacturing line different from the second manufacturing line and is transferred to the second manufacturing line.

39. (New) The manufacturing method for exposure apparatuses according to claim 35, further comprising:

assembling and adjusting a projection system; and

mounting the projection system on the main body frame of the first exposure apparatus in the first manufacturing line,

wherein the adjusted second module is different from the projection system.

40. (New) The manufacturing method for exposure apparatuses according to claim 39, wherein:

the first module which is adjusted in the first manufacturing line includes an illumination system; and

the second module which is adjusted in the second manufacturing line includes a stage system which moves the first object and the second object.

41. (New) A manufacturing method for exposure apparatuses which expose a second object by an exposure beam via first object, comprising:

assembling a main body frame of a first exposure apparatus in a first manufacturing line;

assembling a main body frame of a second exposure apparatus, which is different from the first exposure apparatus, in a second manufacturing line having a sequence that is time-shifted from that of the first manufacturing line;

adjusting, in the second manufacturing line, a module of the first exposure apparatus, which is to be installed to the main body frame of the first exposure apparatus, by using the assembled main body frame of the second exposure apparatus;

removing the adjusted module from the main body frame of the second exposure apparatus, and installing, in the first manufacturing line, the adjusted module to the main body frame of the first exposure apparatus in order to assemble the first exposure apparatus which has a plurality of modules including the adjusted module; and

assembling the second exposure apparatus, which has a plurality of modules, in the second manufacturing line,

wherein the plurality of modules of the second exposure apparatus includes a module which is adjusted in a manufacturing line different from the second manufacturing line and which is transferred to the second manufacturing line.

42. (New) The manufacturing method for exposure apparatuses according to claim 41, further comprising assembling an illumination system into the first exposure apparatus so as to at least a part of the illumination system is mounted on the main body frame of the first exposure apparatus.

43. (New) The manufacturing method for exposure apparatuses according to claim 42, further comprising:

assembling and adjusting a projection system; and

mounting the projection system on the main body frame of the first exposure apparatus and optically adjusting the first exposure apparatus in the first manufacturing line.

44. (New) The manufacturing method for exposure apparatuses according to claim 43, wherein the module of the first exposure apparatus, which is adjusted in the second manufacturing line, includes a stage system which moves the first object and the second object.

45. (New) The manufacturing method for exposure apparatuses according to claim 41, further comprising:

assembling and adjusting a projection system; and

mounting the projection system and at least a part of an illumination system on the main body frame of the first exposure apparatus, and optically adjusting the projection system and the illumination system, respectively, in the first manufacturing line.

46. (New) The manufacturing method for exposure apparatuses according to claim 41, wherein the module of the second exposure apparatus that is adjusted in the manufacturing line different from the second manufacturing line has a same structure as that of the module of the first exposure apparatus that is adjusted in the second manufacturing line.